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25 GHz and 28 GHz wide tuning range 130 nm CMOS VCOs with ferroelectric varactors

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the load of the resonator when the transistors are in the triode region [2].

B. Fabrication of carrier and varactor design

Starting with HR-Si substrates, all processing is carried out in-house at Chalmers. First, a metal layer (M1) consisting of TiO_2 (adhesion layer) and Au is deposited using magnetron sputtering and patterned by ion milling. The BSTO film is subsequently deposited by laser ablation. Next, a layer of SiO_x is introduced in order to prevent DC shorts in large-area decoupling capacitances (via pin-holes in the BSTO film). This layer is removed where the small-sized varactors are formed in order to maximize the tunability of these components. Besides, patterned rings of SiO_2 layer are used as aligning and stop-soldering barriers for mounting of transistor chips. The second metal layer (M2) is deposited by e-beam evaporation and patterned by lift-off. It consists of Ti (improving adhesion to SiO_x) and Au.

The parallel-plate varactors are formed between metal layers M1 and M2. The parallel-plate configuration was chosen because of its high tunability, in comparison to co-planar configuration, at low control voltages. The test varactors sharing substrate with the VCOs have been characterized at 1 MHz. Fig. 2 shows capacitance and loss tangent of a test varactor versus DC bias voltage. The increased loss tangent at positive bottom electrode voltages is caused by increased current through the lowered Ti/BSTO Schottky barrier at the top interface. The small imprint (approximately 0.5 V) is due to asymmetrical top/bottom electrode structure. The capacitance-voltage curve reveals no significant hysteresis. The tunability is 42%. Similar varactors have also been characterized at microwave frequencies, showing a Q-factor higher than 60 and 35 % tunability at frequencies up to 25 GHz [1].

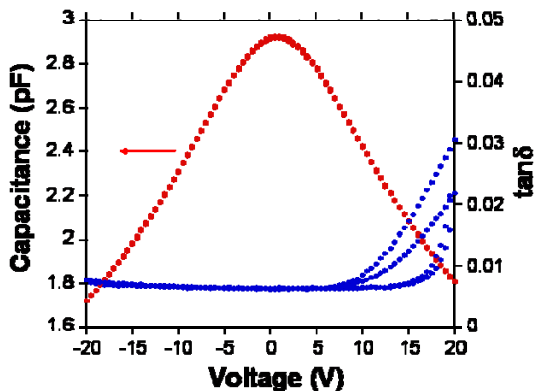


Figure 2. Capacitance and loss tangent of a test varactor versus DC bias voltage.

B. Resonator design

Two different resonators were manufactured, one with a varactor tunable from 50 fF to 90 fF, and one with a 270 fF to 450 fF varactor, Fig. 3. The resonator with the 450 fF varactor has a simulated impedance at resonance of 25Ω , a Q around 20, and a simulated tuning range 80 % larger than for the other one as the transistor and pad capacitances have less influence when such a large varactor is employed. For the resonator based on the 90 fF varactor the simulated impedance is 40Ω and the Q is approximately 30.

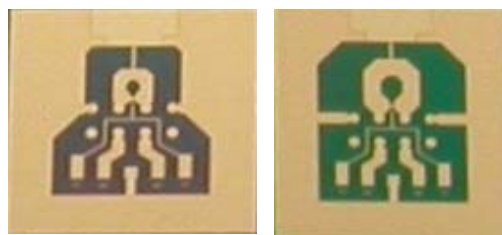


Figure 3. Layouts of the on-carrier resonators. Left: low impedance resonator, Right: high impedance resonator

D. Assembly of module

The flip chip devices have tin-silver-copper bumps manufactured in a high-volume wafer process. Soldering flip chips provides the smoothest process with regards to producibility, self-alignment and repeatability, hence resulting in the lowest cost end-product. The chips were mounted on the carriers using a regular surface mount pick-and-place process. The chip bumps are dipped to a controlled depth in a flux bath, and are then placed on the carrier. The flux is slightly tacky and thus keeps the chip in place while the assembly travels on the conveyor belt through the nitrogen atmosphere soldering oven. The selected flux is a no-clean type, and therefore there was no cleaning step after soldering. The chips are not underfilled at this stage.

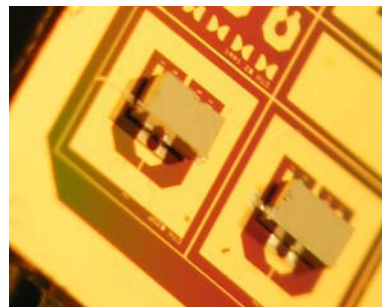


Figure 4. A complete VCO, chip mounted on carrier. The carrier area employed for each design is $1.3 \times 1.4 \text{ mm}^2$

III. MEASURED RESULTS

The performance of the VCOs is summarized in Table I. The phase noise performance has been measured in a setup based on the delay line technique, whereas frequency characteristics were measured with a spectrum analyzer. Fig. 5 shows the measured tuning characteristics of VCO1 and Fig. 6 the tuning characteristics of VCO2. The output power of the VCOs is depicted in Fig. 7. The measured phase noise over tuning range for VCO1 and VCO2 is shown in Fig. 8 and Fig. 9 respectively.

TABLE I
SUMMARY OF VCO PERFORMANCE

	VCO1	VCO2
Current consumption	6.6mA @ 0.8V	12.8mA @ 1.4V
Varactor size	270-450 fF	50-90 fF
Center frequency	28 GHz	24.8 GHz
Tuning range	25.8 -30.5 GHz	23.4-26.1 GHz
Phase Noise@1MHz offset*	-109 dBc/Hz	-117 dBc/Hz
Phase noise@100kHz offset*	-80 dBc/Hz	-89 dBc/Hz

* Phase noise measured at center frequency

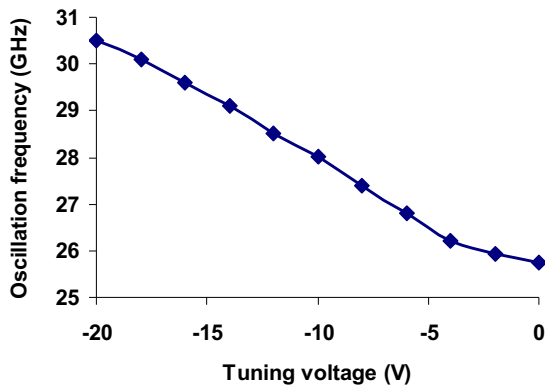


Figure 5. Measured tuning characteristics of VCO1

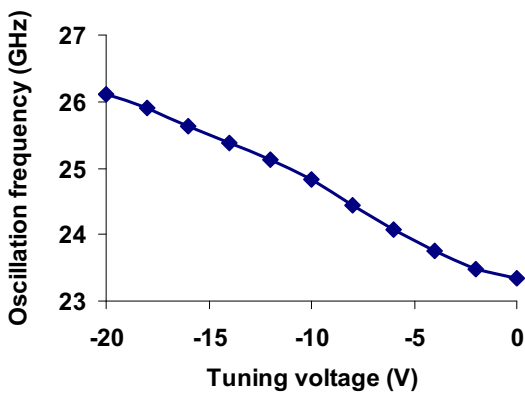


Figure 6. Measured tuning characteristics of VCO2

For VCO2 the phase noise varies less than 2 dB over the tuning range, while it for VCO1 degrades more strongly as the frequency increases. The transition from -30 dB/decade to -20 dB/decade slope at an offset frequency around 1 MHz, indicates a large impact of the CMOS transistors 1/f noise.

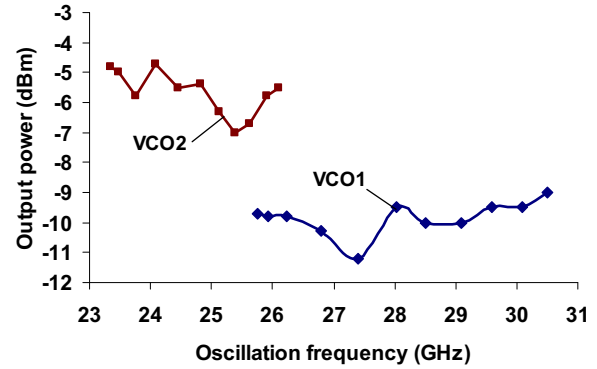


Figure 7. Output power of the VCOs versus frequency.

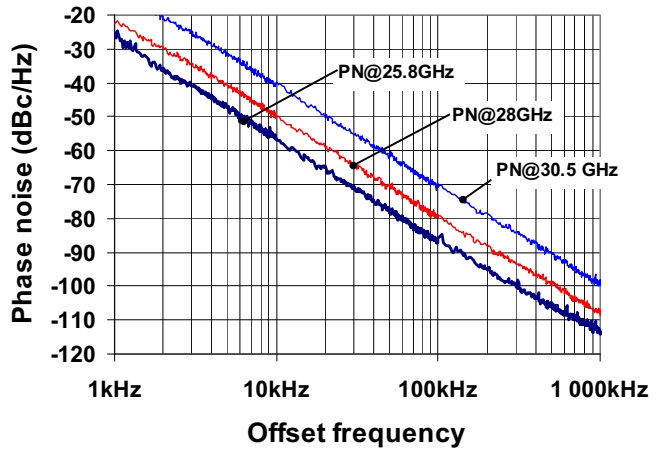


Figure 8. Measured phase noise of VCO1

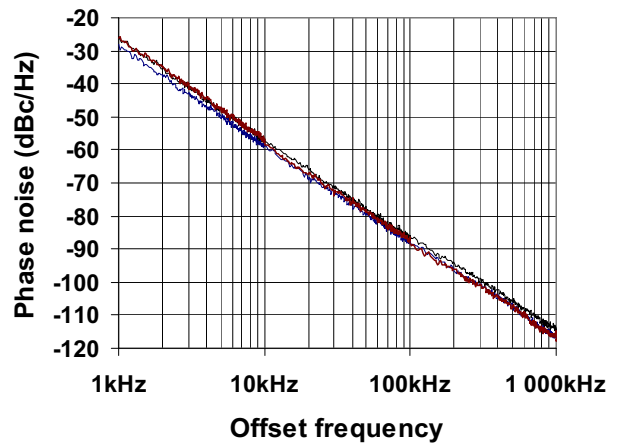


Figure 9. Measured phase noise of VCO2.

TABLE II. SUMMARY OF PUBLISHED VCOS

Ref.	Technology (μm)	F_c (GHz)	Tuning range (%)	V_{DD} (V)	P_{DC} (mW)	PN@1MHz offset(dBc/Hz)	FOM(dB)	FOM _T (dB)
This work	CMOS 0.13	24.8	11	1.4	18	-117*	192	193
This work	CMOS 0.13	28	17	0.8	5.3	-109*	191	195
[3]	SiGe e	16.5	6.7	3	90	-125*	190	186
[4]	CMOS 0.18	40	20**	1.5	27	-100*	178	184
[5]	CMOS 0.09	18	8.3	0.8	4.2	-120*	199	197
[6]	InGaP-GaAs	25	1.6	9	90	-130*	199	183
[7]	CMOS 0.13	18	5.6	1.2	14	-117*	191	186
[8]	CMOS 0.18	21	10.4	1.8	40	-112*	182	182

* measured at center frequency ** not continuously tuned

$$\text{FOM} = -\text{PN} + 20 \log\left(\frac{f_0}{\Delta f}\right) - 10 \log(P_{DC} \text{ (mW)}) \quad \text{FOM}_T = -\text{PN} + 20 \log\left(\frac{f_0 \cdot \text{tuning}(\%)}{\Delta f \cdot 10}\right) - 10 \log(P_{DC} \text{ (mW)})$$

IV. COMPARISON TO PREVIOUSLY PUBLISHED VCO

A comparison with previous published VCOs, Table II, shows that the performance of the VCOs presented in this paper is very competitive. The 28 GHz VCO shows the largest continuous tuning range, while the 25 GHz VCO demonstrates the possibility to achieve excellent phase noise performance and good tuning range simultaneously.

V. CONCLUSION

In this paper the potential of heterogeneous building practice is demonstrated by the design of a high performance VCOs utilizing ferroelectric varactors on a carrier. Identical CMOS chips, consisting only of a few transistors, have been flip-chip mounted on carriers with different resonators. The center frequency and the tuning range are mainly set by the carrier design consisting of a resonator structure including a varactor. The carrier is realized in a two metal layer process including a thin BSTO film between the metals to realize ferroelectric varactors. Measurement results are presented for two designs, one were the CMOS chip is mounted on a carrier optimized for high tuning range, and one were the chip is mounted on a carrier optimized for high Q-value and more moderate tuning range. The design for high tuning range consumes 5.3 mW from a 0.8 V power supply, has a tuning range from 25.8 to 30.5 GHz, and a phase noise of -109 dBc/Hz at 1MHz offset. The design optimized for low phase noise consumes 18 mW from a 1.4 V supply, has a tuning range from 23.5 to 25.2 GHz, and a phase noise of -117 dBc/Hz.

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